L Number	Hits	Search Text	DB	Time stamp
1	1547	(427/552,553,555,558).CCLS.	USPAT;	2004/08/16 09:26
-			US-PGPUB	
2	1093	(427/226).CCLS.	USPAT;	2004/08/16 09:26
			US-PGPUB	
3	2172	(427/248.1,255.18,255.23).CCLS.	USPAT;	2004/08/16 09:26
			US-PGPUB	2004/00/16 00:27
4	3565	(427/256,259,270,271,272,282).CCLS.	USPAT; US-PGPUB	2004/08/16 09:27
_	550	(117/00 05) 0010	USPAT;	2004/08/16 09:27
5	552	(117/88,95).CCLS.	US-PGPUB	2004/00/10 03.27
6	271	(438/503,507).CCLS.	USPAT;	2004/08/16 09:27
0	2/1	(438/303,307).ССШ3.	US-PGPUB	2001,00,20
7	245	(423/349).CCLS.	USPAT;	2004/08/16 09:27
'	5.10	(120,000,000	US-PGPUB	
8	1161	(118/726).CCLS.	USPAT;	2004/08/16 09:27
			US-PGPUB	
9	10032	((427/552,553,555,558).CCLS.)	USPAT;	2004/08/16 09:27
		((427/226).CCLS.)	US-PGPUB	
		((427/248.1,255.18,255.23).CCLS.)		·
		((427/256,259,270,271,272,282).CCLS.)		
		((117/88,95).CCLS.) ((438/503,507).CCLS.)		
		((423/349).CCLS.) ((118/726).CCLS.) ((427/552-553,555,558).CCLS.) and	IISPAT.	2004/-08/-1609:35
		((silicon or Si) near4 (coat\$3 or film or	US-PGPUB	
		layer or deposit\$3 or grow\$3 or \$4CVD))	00 10102	
		and ((ring adj silane) or (cyclic adj		
		silane) or cyclosilane or (cyclical adj		
		silane) or (cyclo adj silane) or		
		cyclopentasilane or Si5H10 or "Si.sub.5		
		H.sub.10" or "Si.sub.5H.sub.10" or (cyclo		
		adj pentasilane) or (cyclo adj penta adj		
		silane) or silylcyclopentasilane or Si6H12		
		or "Si.sub.6H.sub.12" or "Si.sub.6		
		H.sub.12" or (silyl near2		
11	0	cyclopentasilane))	USPAT;	2004/08/16 09:32
11	٠	((427/226).CCLS.) and ((silicon or Si) near4 (coat\$3 or film or layer or	US-PGPUB	2004/08/10 09.32
		deposit\$3 or grow\$3 or \$4CVD)) and ((ring	05 10105	
		adj silane) or (cyclic adj silane) or		
		cyclosilane or (cyclical adj silane) or		ļ
		(cyclo adj silane) or cyclopentasilane or		
		Si5H10 or "Si.sub.5 H.sub.10" or		
		"Si.sub.5H.sub.10" or (cyclo adj	,	
		pentasilane) or (cyclo adj penta adj		
		silane) or silylcyclopentasilane or Si6H12		
	Ì	or "Si.sub.6H.sub.12" or "Si.sub.6   H.sub.12" or (silyl near2		
		cyclopentasilane))		
12	10		USPAT;	2004/08/16 09:33
1	10	((silicon or Si) near4 (coat\$3 or film or	US-PGPUB	= 301, 00, 10 00.00
		layer or deposit\$3 or grow\$3 or \$4CVD))		
		and ((ring adj silane) or (cyclic adj		
	· .	silane) or cyclosilane or (cyclical adj		ľ
		silane) or (cyclo adj silane) or		
		cyclopentasilane or Si5H10 or "Si.sub.5		
		H.sub.10" or "Si.sub.5H.sub.10" or (cyclo		
		adj pentasilane) or (cyclo adj penta adj		
		silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or "Si.sub.6		
		H.sub.12" or (silyl near2		- X.
		cyclopentasilane))		
	L	1 01 010 011 011		

13	0	((427/256,259,270,271,272,282).CCLS.) and	USPAT;	2004/08/16 09:33
		((silicon or Si) near4 (coat\$3 or film or	US-PGPUB	
		layer or deposit\$3 or grow\$3 or \$4CVD))		
		and ((ring adj silane) or (cyclic adj		
1		silane) or cyclosilane or (cyclical adj		
		silane) or (cyclo adj silane) or		
		cyclopentasilane or Si5H10 or "Si.sub.5		
		H.sub.10" or "Si.sub.5H.sub.10" or (cyclo		
		adj pentasilane) or (cyclo adj penta adj		
		silane) or silylcyclopentasilane or Si6H12		
		or "Si.sub.6H.sub.12" or "Si.sub.6		
		H.sub.12" or (silyl near2		
		cyclopentasilane))		1
14	1	((117/88,95).CCLS.) and ((silicon or Si)	USPAT;	2004/08/16 09:33
1 1 1		near4 (coat\$3 or film or layer or	US-PGPUB	
		deposit\$3 or grow\$3 or \$4CVD)) and ((ring	00 2000	i
		adj silane) or (cyclic adj silane) or		
		cyclosilane or (cyclical adj silane) or		
Ì		(cyclo adj silane) or cyclopentasilane or		
		Si5H10 or "Si.sub.5 H.sub.10" or		
		"Si.sub.5H.sub.10" or (cyclo adj		
		pentasilane) or (cyclo adj penta adj	İ	
		silane) or silylcyclopentasilane or Si6H12		
		-or-"Si-sub-6H-sub.12"-or-"Si-sub.6		
		H.sub.12" or (silyl near2		
		cyclopentasilane))		0004/00/16 00 33
15	0	((438/503,507).CCLS.) and ((silicon or	USPAT;	2004/08/16 09:33
		Si) near4 (coat\$3 or film or layer or	US-PGPUB	l
		deposit\$3 or grow\$3 or \$4CVD)) and ((ring		
		adj silane) or (cyclic adj silane) or		
		cyclosilane or (cyclical adj silane) or		
		(cyclo adj silane) or cyclopentasilane or	ļ	
		Si5H10 or "Si.sub.5 H.sub.10" or		
		"Si.sub.5H.sub.10" or (cyclo adj		
		pentasilane) or (cyclo adj penta adj		
		silane) or silylcyclopentasilane or Si6H12		i
	0	or "Si.sub.6H.sub.12" or "Si.sub.6	1	
		H.sub.12" or (silyl near2		
		cyclopentasilane))		
16	0	1	USPAT;	2004/08/16 09:34
1 10		near4 (coat\$3 or film or layer or	US-PGPUB	
	:	deposit\$3 or grow\$3 or \$4CVD)) and ((ring	00 10102	į
-Y-		adj silane) or (cyclic adj silane) or		
				i i
		cyclosilane or (cyclical adj silane) or		
1		(cyclo adj silane) or cyclopentasilane or	1	
		Si5H10 or "Si.sub.5 H.sub.10" or		
		"Si.sub.5H.sub.10" or (cyclo adj		
		pentasilane) or (cyclo adj penta adj		
		silane) or silylcyclopentasilane or Si6H12		
		or "Si.sub.6H.sub.12" or "Si.sub.6		
		H.sub.12" or (silyl near2		
1		cyclopentasilane))		0004/00/16 00 01
17	0		USPAT;	2004/08/16 09:34
		or (cyclic adj silane) or cyclosilane or	US-PGPUB	
		(cyclical adj silane) or (cyclo adj		
1		silane) or cyclopentasilane or Si5H10 or		
1	1	"Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10"		
		or (cyclo adj pentasilane) or (cyclo adj		
		penta adj silane) or silylcyclopentasilane	1	
		or Si6H12 or "Si.sub.6H.sub.12" or		
- 0		"Si.sub.6 H.sub.12" or (silyl near2		
	1	cyclopentasilane))		

		·		
18	near4 (coat\$3 of deposit\$3 or gadj silane) or cyclosilane or (cyclo adj silasilane) or "Si.sub.5H.sub pentasilane) or silane) or silane) or sil		USPAT; US-PGPUB	2004/08/16 09:34
19	0 ((118/726).CC) or (cyclic adj (cyclical adj silane) or cycl "Si.sub.5 H.sub or (cyclo adj penta adj silan or Si6H12 or "S	LS.) and ((ring adj silane) silane) or cyclosilane or silane) or (cyclo adj lopentasilane or Si5H10 or 0.10" or "Si.sub.5H.sub.10" pentasilane) or (cyclo adj ne) or silylcyclopentasilane Si.sub.6H.sub.12" or 0.12" or (silyl near2	USPAT; US-PGPUB	2004/08/16 09:34
20	14 (((427/552,553 ((427/226).CCLS ((427/248.1,255 ((427/256,259,2 ((117/88,95).CC ((423/349).CCLS ((ring adj sila or cyclosilane (cyclo adj sila Si5H10 or "Si.s "Si.sub.5H.sub. pentasilane) or silane) or sily	3,555,558).CCLS.)  3.18,255.23).CCLS.)  270,271,272,282).CCLS.)  CLS.) ((438/503,507).CCLS.)  3.) ((118/726).CCLS.)) and ane) or (cyclic adj silane) or (cyclical adj silane) or sub.5 H.sub.10" or 10" or (cyclo adj cyclopentasilane or sub.5 H.sub.10" or 10" or (cyclo adj cyclopentasilane or Si6H12 sub.12" or "Si.sub.6 silyl near2	USPAT; US-PGPUB	-2004/08/16-10:19

21	^	/ ///27/552 553 555 550\ CCTC \	HCDAT.	2004/00/15 00:25
21	0	( (((427/552,553,555,558).CCLS.) ((427/226).CCLS.)	USPAT; US-PGPUB	2004/08/16 09:35
		((427/248.1,255.18,255.23).CCLS.)		
		((427/256,259,270,271,272,282).CCLS.)		
		((117/88,95).CCLS.) ((438/503,507).CCLS.)		
		((423/349).CCLS.) ((118/726).CCLS.)) and		
		((ring adj silane) or (cyclic adj silane)		į
		or cyclosilane or (cyclical adj silane) or		
		(cyclo adj silane) or cyclopentasilane or		
		Si5H10 or "Si.sub.5 H.sub.10" or		
		"Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj		
		silane) or silylcyclopentasilane or Si6H12		
		or "Si.sub.6H.sub.12" or "Si.sub.6		
		H.sub.12" or (silyl near2		
1		cyclopentasilane))) not ((		
		((427/552,553,555,558).CCLS.) and		
		((silicon or Si) near4 (coat\$3 or film or		1
		layer or deposit\$3 or grow\$3 or \$4CVD))		1
		and ((ring adj silane) or (cyclic adj	1	
		silane) or cyclosilane or (cyclical adj silane) or (cyclo adj silane) or		
		cyclopentasilane or Si5H10 or "Si.sub.5		
		-H.sub.10" or "Si.sub.5H.sub.10" or (cyclo		
		adj pentasilane) or (cyclo adj penta adj		
		silane) or silylcyclopentasilane or Si6H12	1	
		or "Si.sub.6H.sub.12" or "Si.sub.6		
1		H.sub.12" or (silyl near2		
		cyclopentasilane))) or (		
-		((427/248.1,255.18,255.23).CCLS.) and		
}	·	((silicon or Si) near4 (coat\$3 or film or layer or deposit\$3 or grow\$3 or \$4CVD))		
		and ((ring adj silane) or (cyclic adj		
		silane) or cyclosilane or (cyclical adj		
		silane) or (cyclo adj silane) or		
		cyclopentasilane or Si5H10 or "Si.sub.5		j l
		H.sub.10" or "Si.sub.5H.sub.10" or (cyclo		
		adj pentasilane) or (cyclo adj penta adj		`
		silane) or silylcyclopentasilane or Si6H12	*	
		or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2		
		cyclopentasilane))) or (		
		((117/88,95).CCLS.) and ((silicon or Si)		
		near4 (coat\$3 or film or layer or		
		deposit\$3 or grow\$3 or \$4CVD)) and ((ring		
		adj silane) or (cyclic adj silane) or		
		cyclosilane or (cyclical adj silane) or		
		(cyclo adj silane) or cyclopentasilane or		
		Si5H10 or "Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj		
		pentasilane) or (cyclo adj penta adj		
		silane) or silylcyclopentasilane or Si6H12		
		or "Si.sub.6H.sub.12" or "Si.sub.6		
		H.sub.12" or (silyl near2		
		cyclopentasilane))))		
22	41	((silicon or Si or polysilicon) near4	EPO; JPO;	2004/08/16 09:43
		(coat\$3 or film or layer or deposit\$3 or	DERWENT;	
[		grow\$3 or \$4CVD)) and ((ring adj silane)	IBM_TDB	
		or (cyclic adj silane) or cyclosilane or (cyclical adj silane) or (cyclo adj		
		silane) or cyclopentasilane or Si5H10 or		
		"Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10"		
		or (cyclo adj pentasilane) or (cyclo adj		
		penta adj silane) or silylcyclopentasilane		
		or Si6H12 or "Si.sub.6H.sub.12" or		
		"Si.sub.6 H.sub.12" or (silyl near2		
		cyclopentasilane))		

23	8	(((silicon or Si or polysilicon) near4 (coat\$3 or film or layer or deposit\$3 or grow\$3 or \$4CVD)) and ((ring adj silane)	EPO; JPO; DERWENT; IBM_TDB	2004/08/16 09:44
		or (cyclic adj silane) or cyclosilane or (cyclical adj silane) or (cyclo adj		
		silane) or cyclopentasilane or Si5H10 or		
		"Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj		
		penta adj silane) or silylcyclopentasilane		
		or Si6H12 or "Si.sub.6H.sub.12" or		
		"Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))) and (inactive or SAM		
		or monolayer or active or ((mono or		
		molecular) adj (layer or film)) or (self adj assembl\$4) or mask\$3 or pattern\$3 or		
		selectively)		
24	33	(((silicon or Si or polysilicon) near4	EPO; JPO;	2004/08/16 09:39
		<pre>(coat\$3 or film or layer or deposit\$3 or grow\$3 or \$4CVD)) and ((ring adj silane)</pre>	DERWENT; IBM TDB	
		or (cyclic adj silane) or cyclosilane or		
		(cyclical adj silane) or (cyclo adj silane) or cyclopentasilane or Si5H10 or		
		"Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10"		
		or (cyclo adj pentasilane) or (cyclo adj	·	
		penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or		
		"Si.sub.6 H.sub.12" or (silyl near2		
		<pre>cyclopentasilane))) not (((silicon or Si or polysilicon) near4 (coat\$3 or film or</pre>		
		layer or deposit\$3 or grow\$3 or \$4CVD))		
		and ((ring adj silane) or (cyclic adj silane) or cyclosilane or (cyclical adj		
		silane) or cyclo adj silane) or		
		cyclopentasilane or Si5H10 or "Si.sub.5		
		H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj penta adj		
		silane) or silylcyclopentasilane or Si6H12		
		or "Si.sub.6H.sub.12" or "Si.sub.6 H.sub.12" or (silyl near2		
		cyclopentasilane))) and (inactive or SAM		
		or monolayer or active or ((mono or molecular) adj (layer or film)) or (self		
		adj assembl\$4) or mask\$3 or pattern\$3 or		
0.5	1.00	selectively))		
25	168	((silicon or Si or polysilicon) near4 (coat\$3 or film or layer or deposit\$3 or	USPAT; US-PGPUB	2004/08/16 09:43
		grow\$3 or \$4CVD)) and ((ring adj silane)		
		or (cyclic adj silane) or cyclosilane or (cyclical adj silane) or (cyclo adj		
		silane) or cyclopentasilane or Si5H10 or	-	
		"Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10" or (cyclo adj pentasilane) or (cyclo adj	-	
		penta adj silane) or silylcyclopentasilane		
		or Si6H12 or "Si.sub.6H.sub.12" or	İ	
		"Si.sub.6 H.sub.12" or (silyl near2 cyclopentasilane))		
26	133	(((silicon or Si or polysilicon) near4	USPAT;	2004/08/16 09:44
		<pre>(coat\$3 or film or layer or deposit\$3 or grow\$3 or \$4CVD)) and ((ring adj silane)</pre>	US-PGPUB	
		or (cyclic adj silane) or cyclosilane or		
		(cyclical adj silane) or (cyclo adj silane) or cyclopentasilane or Si5H1O or		
		"Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10"		
		or (cyclo adj pentasilane) or (cyclo adj		
		penta adj silane) or silylcyclopentasilane or Si6H12 or "Si.sub.6H.sub.12" or		
		"Si.sub.6 H.sub.12" or (silyl near2		
		cyclopentasilane))) and (inactive or SAM or monolayer or active or ((mono or		
		molecular) adj (layer or film)) or (self		
		<pre>adj assembl\$4) or mask\$3 or pattern\$3 or selectively)</pre>		
L	.L	DOTOCTIVETY	L	

27	133		USPAT;	2004/08/16 09:55
		(coat\$3 or film or layer or deposit\$3 or	US-PGPUB	
		grow\$3 or \$4CVD)) and ((ring adj silane)	;	
		or (cyclic adj silane) or cyclosilane or		
		(cyclical adj silane) or (cyclo adj		
		silane) or cyclopentasilane or Si5H10 or		
		"Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10"		
		or (cyclo adj pentasilane) or (cyclo adj		
		penta adj silane) or silylcyclopentasilane		
		or Si6H12 or "Si.sub.6H.sub.12" or		
		"Si.sub.6 H.sub.12" or (silyl near2		
		cyclopentasilane))) and (inactive or SAM		
		or monolayer or active or ((mono or		
		molecular) adj (layer or film)) or (self		
		adj assembl\$4) or mask\$3 or pattern\$3 or		
		selectively or photomask\$3)		
28	35		USPAT;	2004/08/16 09:58
		(coat\$3 or film or layer or deposit\$3 or	US-PGPUB	
		grow\$3 or \$4CVD)) and ((ring adj silane)		
		or (cyclic adj silane) or cyclosilane or		
	İ	(cyclical adj silane) or (cyclo adj		
		silane) or cyclopentasilane or Si5H10 or		
		"Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10"		
		or -(cyclo-adj-pentasilane)or-(cyclo adj		
		penta adj silane) or silylcyclopentasilane		
		or Si6H12 or "Si.sub.6H.sub.12" or		
		"Si.sub.6 H.sub.12" or (silyl near2		
		cyclopentasilane))) not (((silicon or Si		
		or polysilicon) near4 (coat\$3 or film or		
		layer or deposit\$3 or grow\$3 or \$4CVD))	-	
		and ((ring adj silane) or (cyclic adj		
	{	silane) or cyclosilane or (cyclical adj		
		silane) or (cyclo adj silane) or		
		cyclopentasilane or Si5H10 or "Si.sub.5		
		H.sub.10" or "Si.sub.5H.sub.10" or (cyclo		
		adj pentasilane) or (cyclo adj penta adj		
į	İ	silane) or silylcyclopentasilane or Si6H12		
		or "Si.sub.6H.sub.12" or "Si.sub.6		
		H.sub.12" or (silyl near2		
		cyclopentasilane))) and (inactive or SAM		
		or monolayer or active or ((mono or		
	İ	molecular) adj (layer or film)) or (self		
		adj assembl\$4) or mask\$3 or pattern\$3 or		
		selectively or photomask\$3))		
29	2		USPAT;	2004/08/16 09:59
		((427/226).CCLS.)	US-PGPUB	
1		((427/248.1,255.18,255.23).CCLS.)	***	
		((427/256,259,270,271,272,282).CCLS.)		
		((117/88,95).CCLS.) ((438/503,507).CCLS.)		
		((423/349).CCLS.) ((118/726).CCLS.)) and		
		(active with inactive with (\$4CVD or		
		(vapor adj deposit\$3)))		
30	15	(active with inactive with (\$4CVD or	USPAT;	2004/08/16 10:00
		(vapor adj deposit\$3)))	US-PGPUB	
31	13	((active with inactive with (\$4CVD or	USPAT;	2004/08/16 09:59
		(vapor adj deposit\$3)))) not	US-PGPUB	
		((((427/552,553,555,558).CCLS.)		
		((427/226).CCLS.)		
		((427/248.1,255.18,255.23).CCLS.)		
		((427/256,259,270,271,272,282).CCLS.)		
		((117/88,95).CCLS.) ((438/503,507).CCLS.)		
		((423/349).CCLS.) ((118/726).CCLS.)) and		
		(active with inactive with (\$4CVD or		
		(vapor adj deposit\$3))))		,
32	11	(active with inactive with (\$4CVD or	EPO; JPO;	2004/08/16 10:01
		(vapor adj deposit\$3)))	DERWENT;	
			IBM TDB	
	•	termination of the second of t	·	<u> </u>

33	147	((118/726).CCLS.) and ((crucible or	USPAT;	2004/08/16 10:17
		evaporator or source or substrate or	US-PGPUB	
		liquid or solution) near7 (pattern\$3 or		
		mask\$3 or SAM or photomask\$3 or monolayer		<u>.</u>
		or ((mono or molecular) near2 (layer or		
		film)) or (self adj assembl\$3)))		0004/00/16 10 00
34	25898	((Si or silicon or polysilicon) near4	USPAT;	2004/08/16 10:23
		(coat\$3 or deposit\$3 or film or layer or	US-PGPUB;	
		grow\$3 or \$4CVD) with (\$4CVD or (vapor adj	EPO; JPO;	
		deposit\$3)) same (selective\$3 or pattern\$3	DERWENT;	
25	0.50	or portion))	IBM_TDB	2004/00/16 10:10
35	253	(((Si or silicon or polysilicon) near4	USPAT;	2004/08/16 10:19
		(coat\$3 or deposit\$3 or film or layer or	US-PGPUB;	
		grow\$3 or \$4CVD) with (\$4CVD or (vapor adj	EPO; JPO;	
	-	deposit\$3)) same (selective\$3 or pattern\$3	DERWENT;	
		or portion))) and	IBM_TDB	
		(((427/552,553,555,558).CCLS.)		
		((427/226).CCLS.) ((427/248.1,255.18,255.23).CCLS.)		
		((427/246.1,255.16,255.25).ccls.)		
		((117/88,95).CCLS.) ((438/503,507).CCLS.)		
		((423/349).CCLS.) ((118/726).CCLS.))		
36	18	(((Si or silicon or polysilicon) near4	USPAT;	2004/08/16 10:20
		-(coat\$3-or deposit\$3-or film-or layer-or	-US-PGPUB	2003700710 10.20
		grow\$3 or \$4CVD) with (\$4CVD or (vapor adj	00 10105	
		deposit\$3)) same (selective\$3 or pattern\$3		
		or portion))) and ((ring adj silane) or		
		(cyclic adj silane) or cyclosilane or		
		(cyclical adj silane) or (cyclo adj	**	
		silane) or cyclopentasilane or Si5H10 or		
		"Si.sub.5 H.sub.10" or "Si.sub.5H.sub.10"		
		or (cyclo adj pentasilane) or (cyclo adj		
		penta adj silane) or silylcyclopentasilane		
		or Si6H12 or "Si.sub.6H.sub.12" or		
		"Si.sub.6 H.sub.12" or (silyl near2		
		cyclopentasilane))		
37	21		USPAT;	2004/08/16 10:28
1		(coat\$3 or deposit\$3 or film or layer or	US-PGPUB;	
		grow\$3 or \$4CVD) with (\$4CVD or (vapor adj	EPO; JPO;	
		deposit\$3)) same (selective\$3 or pattern\$3	DERWENT;	
		or portion))) and ((deposit\$3 or apply\$3	IBM_TDB	
		or arrang\$3 or place or placed or placing		
	*	or print\$3) near4 (liquid or solution or		
		precursor or \$10silane) near4 (substrate		
		or base or crucible or evaporator or		
		source or vaporizer or vaporizor) with		
		(evaporat\$3 or vaporize))	1	
38	41	((deposit\$3 or apply\$3 or arrang\$3 or	USPAT;	2004/08/16 10:29
		place or placed or placing or print\$3)	US-PGPUB;	
		near4 (liquid or solution or precursor or	EPO; JPO;	
		\$10silane) near4 (substrate or base or	DERWENT;	
		crucible or evaporator or source or	IBM_TDB	
		vaporizer or vaporizor) with (evaporat\$3		
		or vaporize) with (pattern\$3 or		
		selective\$3))	L	l